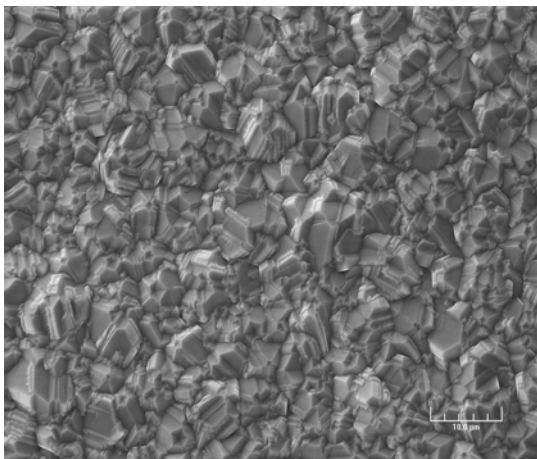


# BJS 150

## Microwave PECVD of single or polycrystalline diamond films



Hydrogen methane plasma



Deposition of polycrystalline diamond films  
Deposition rate = 6.5  $\mu\text{m}/\text{h}$

### Specifications

- 6'' chamber
- Base vacuum  $< 10^{-7}$  Torr
- Uniformity on 2'' :  $\pm 5\%$
- Maximum power density 80 W/cm<sup>3</sup>
- Switching microwave power supply, 2,45GHZ, 6kw continuous or pulsable
- Gaz lines for doping
- Pressure regulation
- Gaz shower at substrate level
- Deposition rate up to 15  $\mu\text{m}/\text{h}$
- Less than 1 ppb of N<sub>2</sub> impurities in layers
- « Bell Jar » type equipment to reduce memory effect in case of layer doping
- Ergonomic and user-friendly
- Computer control with manual, semi-automatic and fully automatic modes

### Applications

- Tribologic coatings
- Optical windows
- Substrates
- Power electronics
- Heat dissipation
- Sensors



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